

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Inventor(s) : Volker BECKER et al.  
Serial No. : To Be Assigned  
Filed : Herewith  
For : **DEVICE AND METHOD FOR HIGH-RATE  
ETCHING A SUBSTRATE USING A PLASMA  
ETCHING SYSTEM AND DEVICE AND  
METHOD FOR IGNITING A PLASMA AND  
ADJUSTING UPWARD OR PULSING THE  
PLASMA POWER**  
  
Examiner : To Be Assigned  
Art Unit : To Be Assigned

Assistant Commissioner for Patents  
Washington, D.C. 20231

**PRELIMINARY AMENDMENT**

SIR:

Kindly amend the above-identified application before examination as set forth below.

**IN THE SPECIFICATION:**

On page 1, before line 5, insert: FIELD OF THE INVENTION--.

On page 1, line 13, delete "Related Art" and insert: DESCRIPTION OF  
RELATED ART--.

On page 3, line 13, change "German Patent 41 42 045 C1" to German  
Patent 42 41 045 C1--.

On page 4, line 19, insert: SUMMARY OF THE INVENTION--.

On page 4, line 28, delete "Advantages of the Invention".